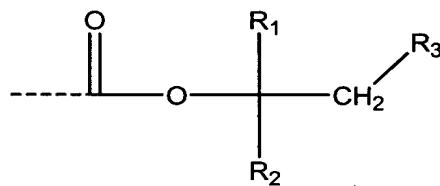


Claims

What is claimed is:

1. A process for fabricating an electronic device comprising:
 - a) coating an electronic device structure with a positive photo-imageable
- 5 protective layer comprising a polymer in which at least 50 mole percent of the monomers in the polymer comprise a structure selected from the group consisting of:

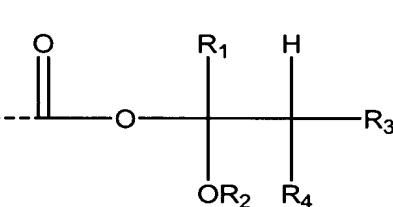
10



where R₁ is hydrogen or lower alkyl; R₂ is a lower alkyl; and R₃ is

- 15 hydrogen or a lower alkyl where the definition of lower alkyl includes alkyl groups having 1 to 6 linear or cyclic carbon atoms;

20

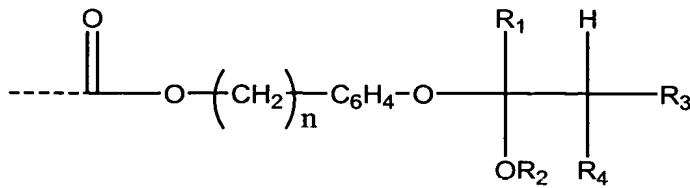


where R₁ is hydrogen or lower alkyl; R₂ is a lower alkyl; and R₃ and R₄ are independently hydrogen or a lower alkyl where the definition of lower alkyl includes alkyl groups having 1 to 6 carbon atoms and the joining of R₁ and R₂, or R₁ and either R₃ or R₄, or R₂ and either R₃ or R₄ to form a 5-, 6-, or 7-membered ring; and

30

c)

5



10 where R_1 is hydrogen or lower alkyl; R_2 is a lower alkyl; and R_3 and R_4 are independently hydrogen or a lower alkyl where the definition of lower alkyl includes alkyl groups having 1 to 6 carbon atoms and the joining of R_1 and R_2 , or R_1 and either R_3 or R_4 , or R_2 and either R_3 or R_4 to form a 5-, 6-, or 7-membered ring.

15

2. The process of Claim 1 wherein the positive photo-imageable protective layer comprises a polymer selected from the group consisting of 1-ethoxyethyl methacrylate, 1-ethoxyethyl acrylate, 1-butoxyethyl methacrylate, 1-butoxyethyl acrylate, 1-ethoxy-1-propyl methacrylate, 1-ethoxy-1-propyl acrylate, tetrahydropyranyl methacrylate, tetrahydropyranyl acrylate, tetrahydropyranyl p-vinylbenzoate, 1-ethoxy-1-propyl p-vinylbenzoate, 4-(2-tetrahydropyranyloxy)benzyl methacrylate, 4-(2-tetrahydropyranyloxy)benzyl acrylate, 4-(1-butoxyethoxy)benzyl methacrylate, 4-(1-butoxyethoxy)benzyl acrylate t-butyl methacrylate, t-butyl acrylate, neopentyl methacrylate, neopentyl acrylate, 1-Bicyclo{2,2,2}octyl methacrylate (or acrylate) and their derivatives, 1-Bicyclo{2,2,1}heptyl methacrylate (or acrylate) and their derivatives, 1-Bicyclo{2,1,1}hexyl methacrylate (or acrylate) and their derivatives, 1-Bicyclo{1,1,1}pentyl methacrylate (or acrylate) and their derivatives and 1-adamantyl methacrylate (or acrylate) and their derivatives.

3. The process for fabricating an electronic device of Claim 1 comprising coating an electronic device structure with a positive photo-imageable protective layer comprising an acrylic polymer wherein at least 50% of the monomer segments are derived from the positive photo-imageable polymers of claim 2.

4. The process of Claim 1 or Claim 2 further comprising adding to the photo-imageable polymer 0.5-30 mole% of photoacid generator and 10-1000 ppm of photosensitizer.

10

5. An electronic device fabricated by a process selected from the group consisting of the process of Claims 1, 2 , 3 or 4.